

ABSTRACT OF THE DISCLOSURE

The present invention relates to a photolithography processing system and a method thereof that is able to detect the presence of impure matters remaining on the surface of a wafer in the process of forming a pattern mask and then determine a subsequent processing step of the wafer with reference to the result of the detection. The photolithography processing system includes: a table positioned near a loader where a carrier is positioned for supporting a wafer that is being transported by a robot; a plurality of illumination tools positioned for illuminating the surface of the wafer positioned on the table; a camera for taking pictures of the surface of the wafer; and a controller for controlling operations of the robot, the illumination tools and for detecting the presence of impure matters on the surface of the wafer.